

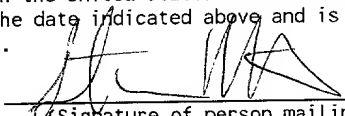
Certificate of Mailing

TB 621 467 10X US  
"Express Mail" mailing number

May 4, 2001  
Date of Deposit

I hereby certify that this application is being deposited with the United States Postal Service "Express Mail Post Office to Addressee" service under 37 CFR 1.10 on the date indicated above and is addressed to the Commissioner of Patents and Trademark, Washington, D.C. 20231.

Steven M. Mitchell  
(Typed or printed name of person mailing application)

  
(Signature of person mailing application)

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of:	:	Date: May 4, 2001
Hemphill, et al.	:	
Serial No: to be assigned	:	Group Art Unit: not known
Filed: herewith	:	
For: "Non-Uniform Etching Of Anode Foil To Produce Higher Capacitance Gain Without Sacrificing Foil Strength"	:	Examiner: not yet known

PRELIMINARY AMENDMENT

Honorable Assistant Commissioner for Patents  
Washington, D.C. 20231

Sir:

Please amend the above-captioned patent application as follows:

In the specification:

On page 3, please replace paragraph 7 with the following rewritten paragraph:

The ideal etching structure is a pure tunnel-like etch with defined and uniform tunnel diameters and without any undesirable pitting of the foil. As tunnel density (*i.e.*, the number of tunnels per square centimeter) is increased, a corresponding enlargement of the overall surface area will occur. Larger surface area results in higher overall capacitance. However, as tunnel density increases, more of the aluminum foil is removed, reducing the strength of the remaining foil. Therefore a compromise must be made between foil strength and capacitance gain.

Attached hereto is a marked-up version of the changes made to the specification by the preliminary amendment. The attachment is captioned "VERSION WITH MARKINGS TO SHOW CHANGES MADE".

Please charge any fees or credit overpayment to Deposit Account No. 22-0265. If any addition extension fee is required, please charge to Deposit Account No. 22-0265. This form is submitted in triplicate.

Respectfully submitted,

  
Steven M. Mitchell  
Reg. No. 31,857  
Attorney for Applicant

PACESETTER, INC.  
701 E. Evelyn Avenue  
Sunnyvale, CA 94086  
Telephone: (408) 522-6101  
Date: May 4, 2001

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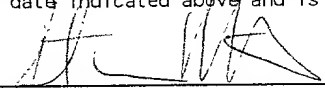
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